

# First Results of GaInP-Based Light Sensors for High Energy Physics

Grace E. Cummings, Bob Hirosky, Thomas Anderson,  
Nicholas Anderson

LightSpin Technologies, Inc.



# Why GaInP?

High Energy Physics experiments are high radiation environments. While SiPMs lead in HEP light detection, they are not optimized for radiation hardness. We are looking for Geiger Mode APDs made from materials designed to withstand our harsh radiation conditions.

**Large Band Gap**  
=  
**Low Thermal Noise**



Harder for thermally  
generated electrons to  
produce signal

**Low Carrier  
Concentration**  
=  
**Less sensitivity to  
induced defects**

**Commercially Available  
Substrate**  
=  
**Production ready  
material**

# The Devices

10 devices per chip, two new generations of device

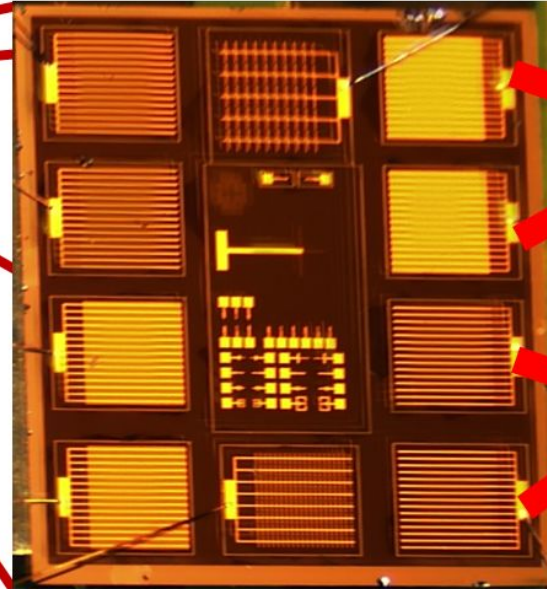
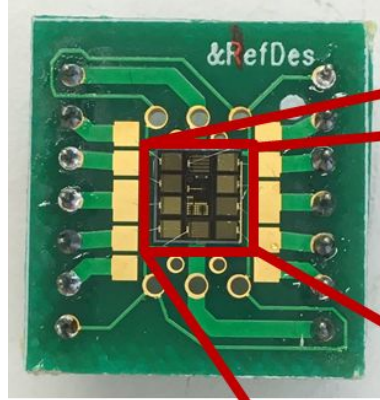
## Gen5.1

- AlGaAs window
- Anti-reflective coating

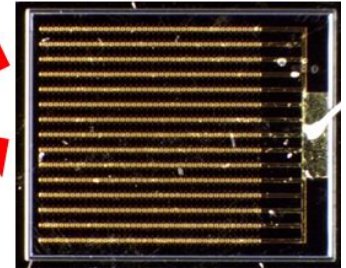
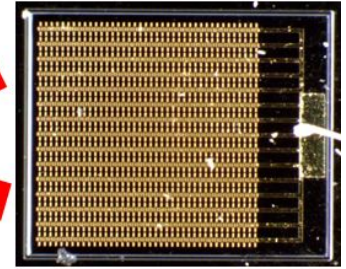
## Gen5.2

- Different manufacturer
- AlInP window
- Improvement on fill factor
- Improved anti-reflective coating

New to this run: bypass capacitors to increase the speed and amplitude of the signal pulse.

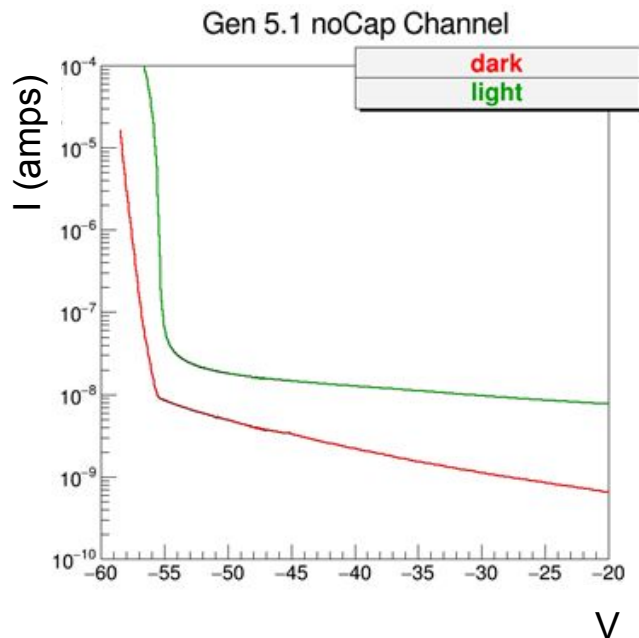


Channels (devices)  
with bypass capacitors



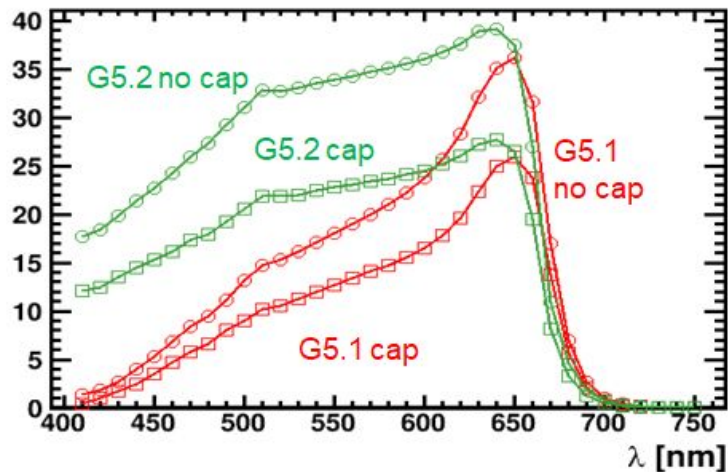
Channels without  
bypass capacitors

# Light Sensitivity



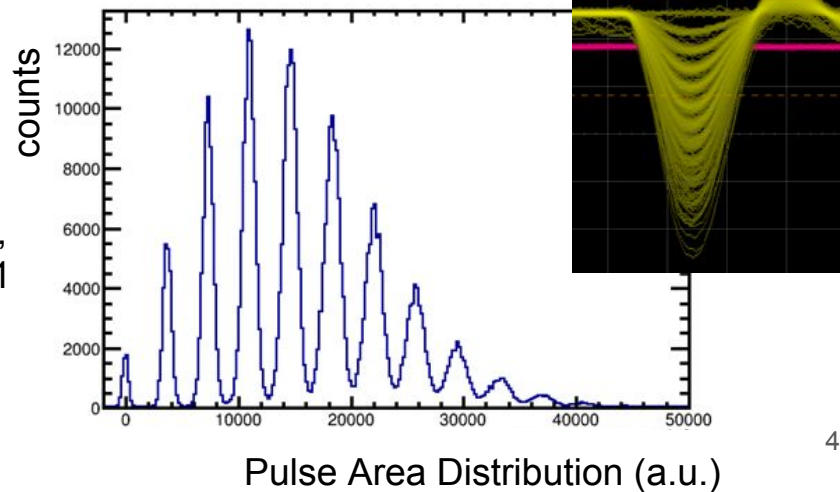
Characteristic “hockey stick” shape of IV curves. Gen5.1 has breakdowns around 55 V, Gen5.2 around 45 V

QE



External quantum efficiency higher for Gen5.2 due to improved anti-reflective coating. Capacitor channels have lower active area.

Multiphoton peak resolution, better in Gen5.1

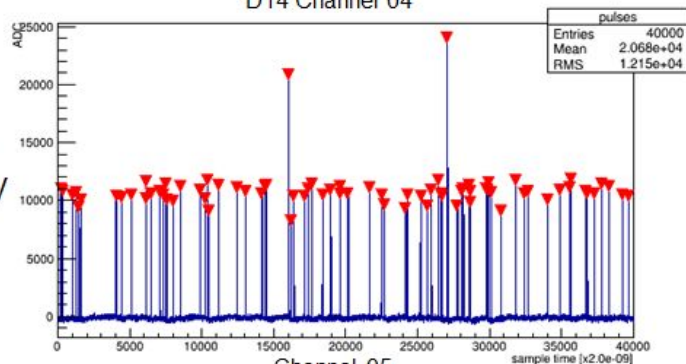


# Dark Pulse Comparisons

Gen5.1

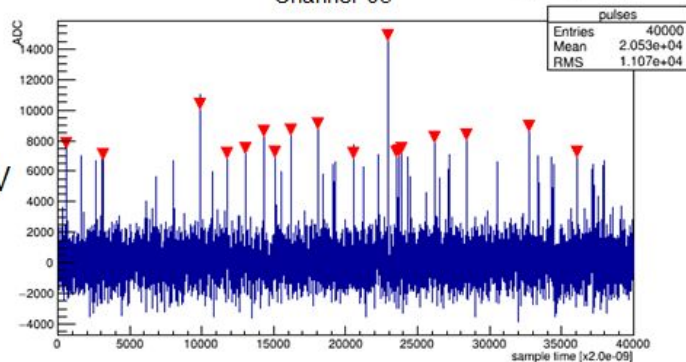
D14 Channel 04

$V_{ex} = 0.76 \text{ V}$



Channel 05

$V_{ex} = 0.85 \text{ V}$



Capacitor  
Channels

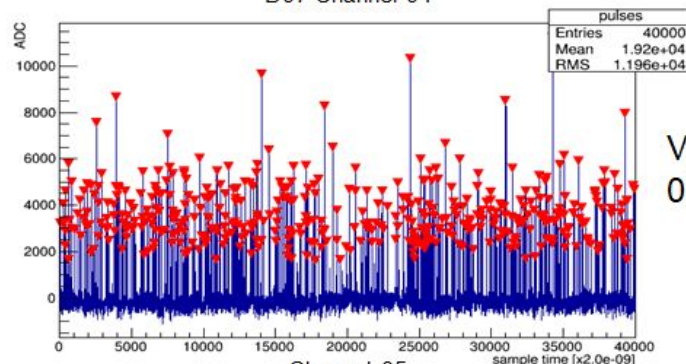
Gen5.1  
Quieter

Non-  
Capacitor  
Channels

Gen5.2

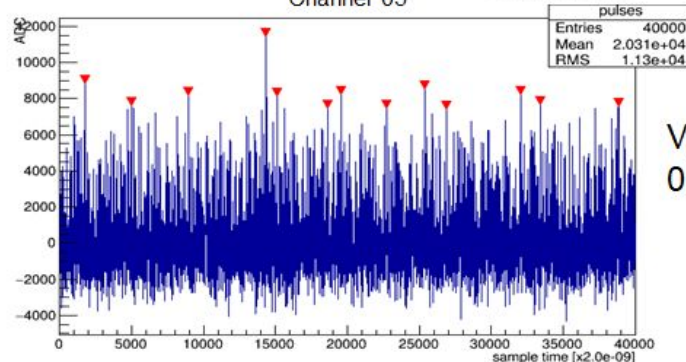
D07 Channel 04

$V_{ex} = 0.12 \text{ V}$



Channel 05

$V_{ex} = 0.12 \text{ V}$



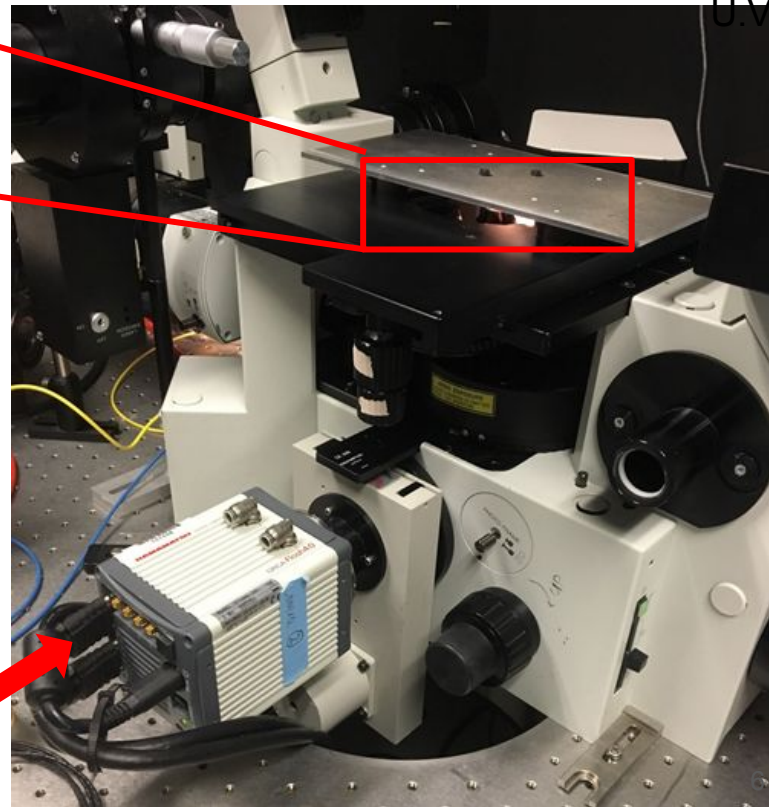


# Using light to probe damage

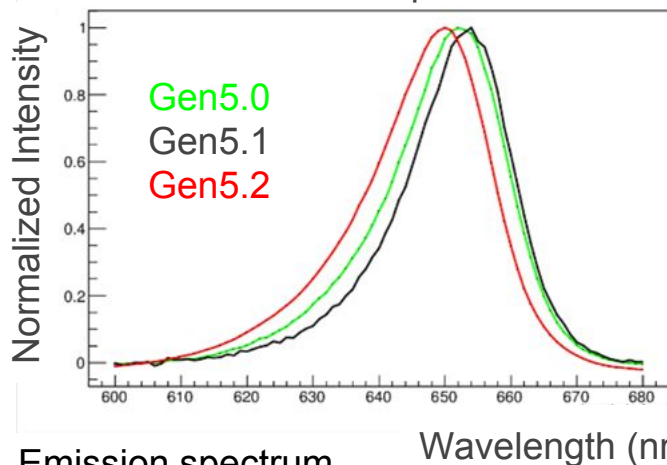
Took 10  
second  
exposures



Total Internal Reflectance Fluorescence (TIRF)  
microscope at the W.M Keck Center for Cellular Imaging at  
U.Va



Emission Spectra

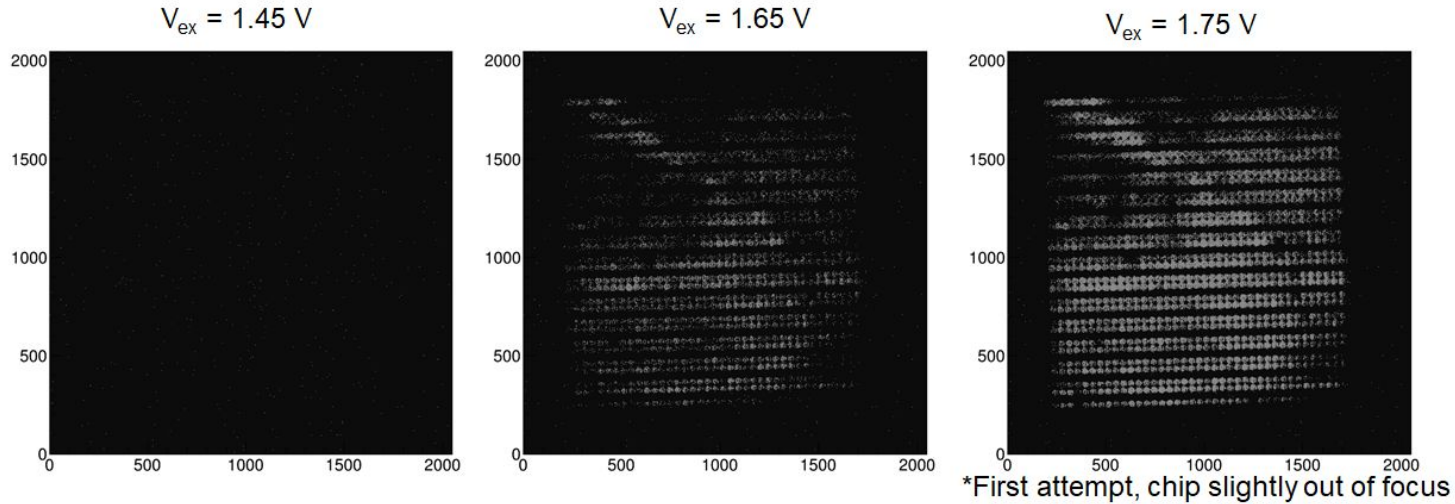


Emitted light  
peaks in the red,  
so used a red light  
to focus

Emission spectrum  
consistent with 1.9  
eV band gap.

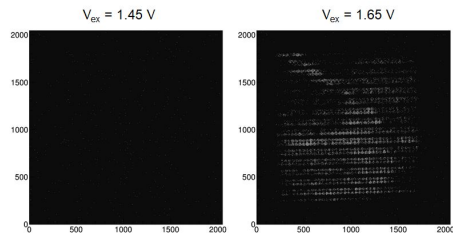
Hamamatsu ORCA-Flash4.0 CCD  
4 Mpix, QE > 70%

# First Illuminations



On non-irradiated chip, higher overvoltage needed to emit light. Light appears to come uniformly out of entire active area.

# First Illuminations

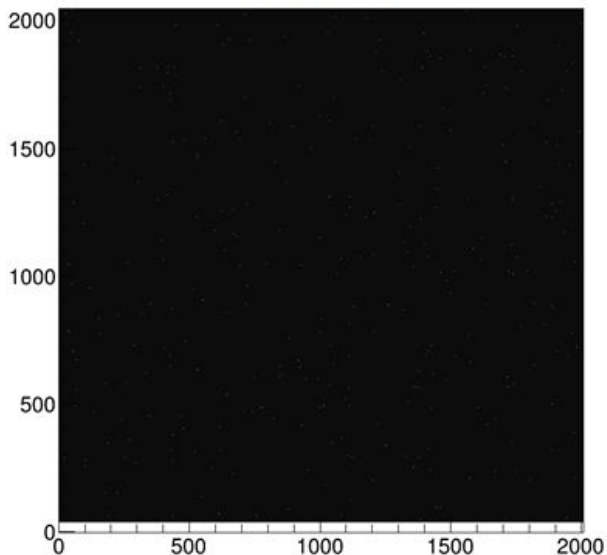


Gen5.1

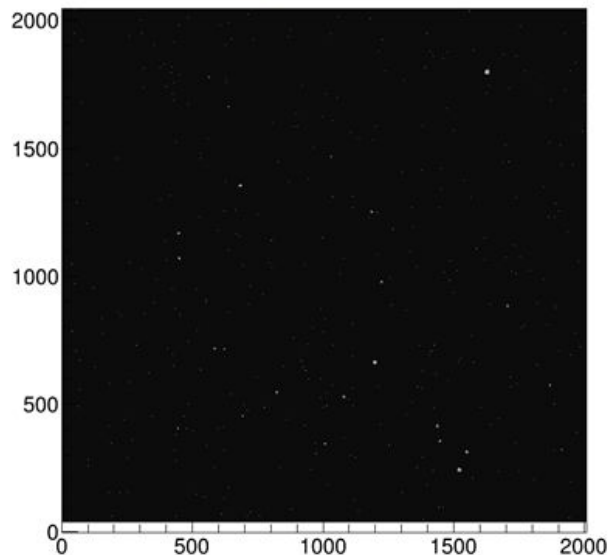
Gen5.2

On non-irradiated chip, we saw hotspots at standard overvoltages, indicating crystal defects. **Source of increased dark count rate.**

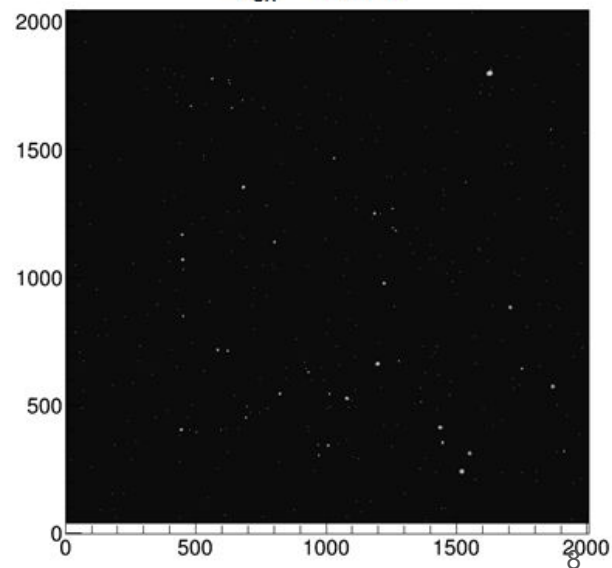
No voltage applied



$V_{\text{ex}} = 0.3 \text{ V}$

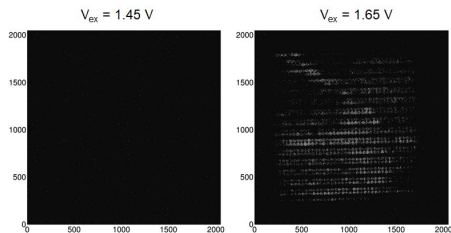


$V_{\text{ex}} = 0.5 \text{ V}$





# First Illuminations

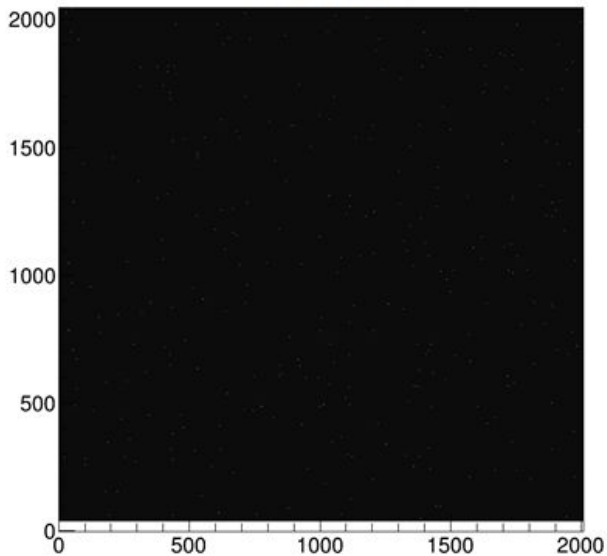


Gen5.1

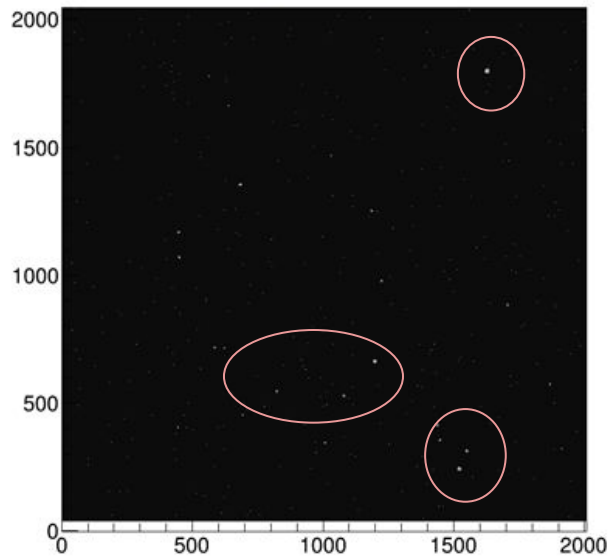
Gen5.2

On non-irradiated chip, we saw hotspots at standard overvoltages, indicating crystal defects. **Source of increased dark count rate.**

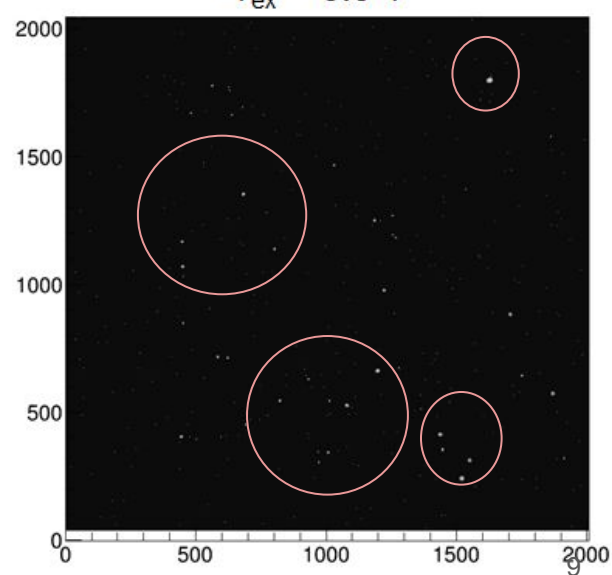
No voltage applied



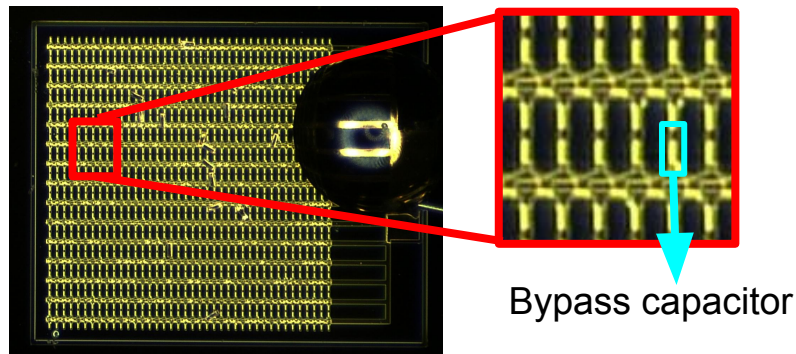
$V_{\text{ex}} = 0.3 \text{ V}$



$V_{\text{ex}} = 0.5 \text{ V}$

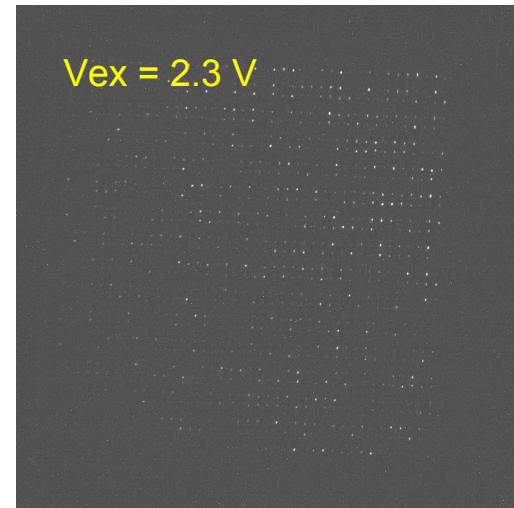


# Gen5.1 capacitor channel damage



At first, looks like damage is clustered near the capacitor

$V_{ex} = 2.3 \text{ V}$



$V_{ex} = 1.3 \text{ V}$

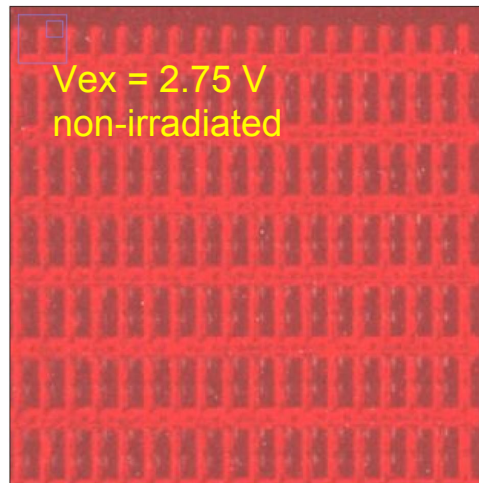
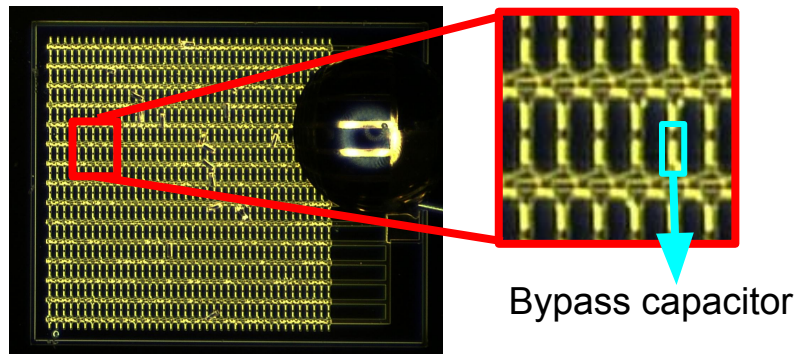
$V_{ex} = 1.8 \text{ V}$

$V_{ex} = 2.3 \text{ V}$

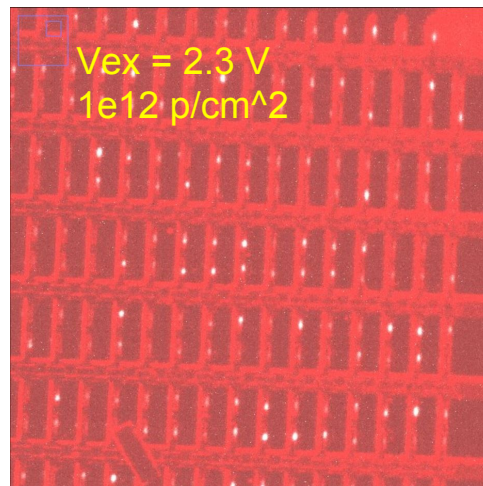
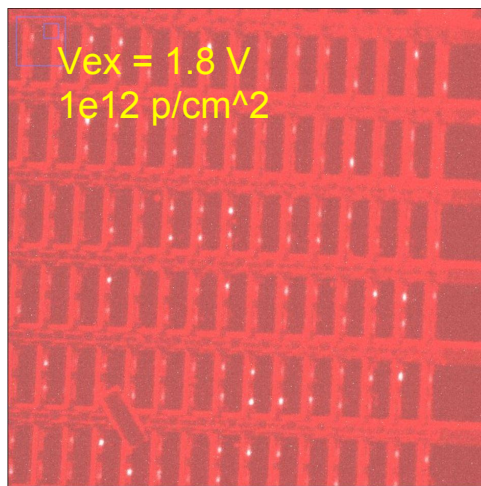
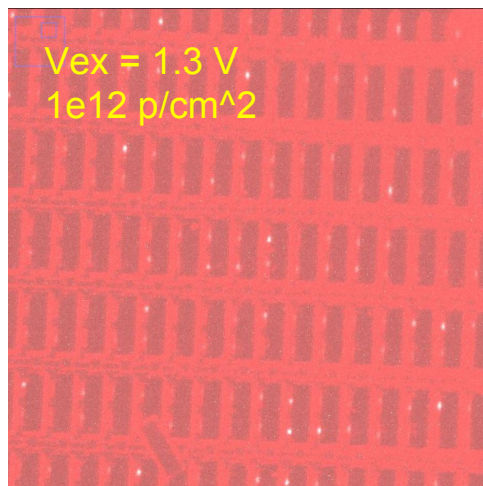
Received  $1e12$  p/cm<sup>2</sup>

Damage across entire array

# Gen5.1 capacitor channel

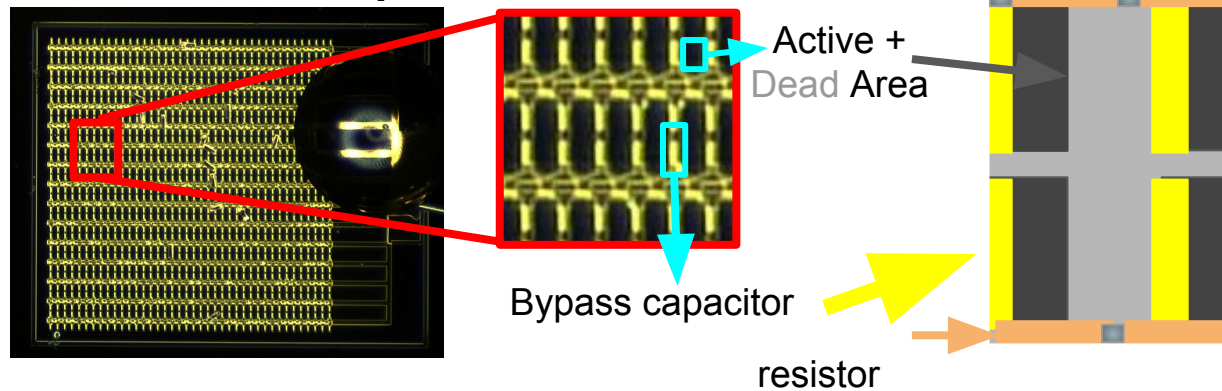


However, radiation damage seems to be in same place as emitted light of unirradiated chips





# Gen5.1 capacitor channel



$V_{ex} = 1.3 \text{ V}$   
 $1\text{e}12 \text{ p/cm}^2$

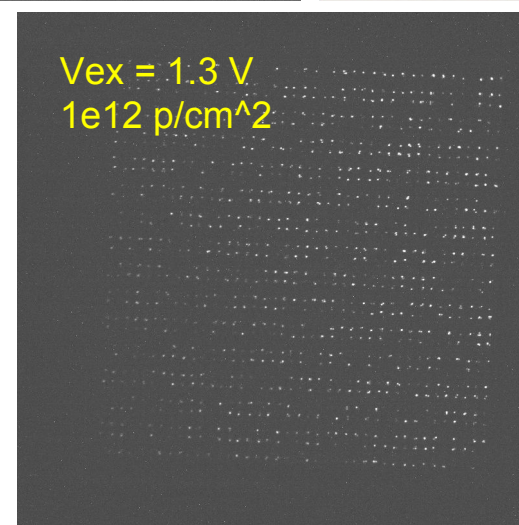
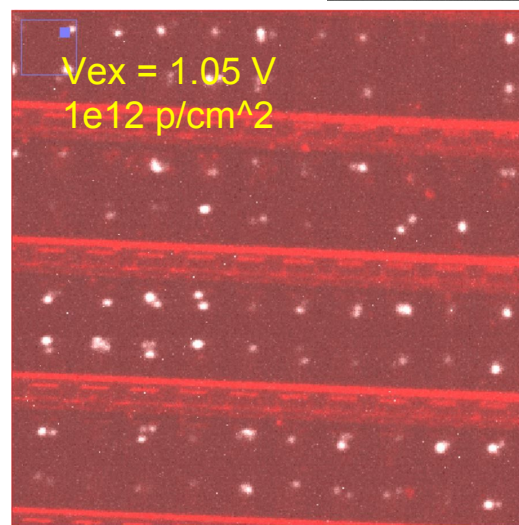
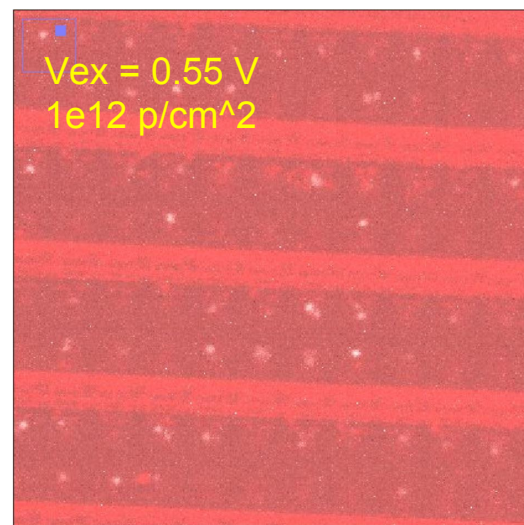
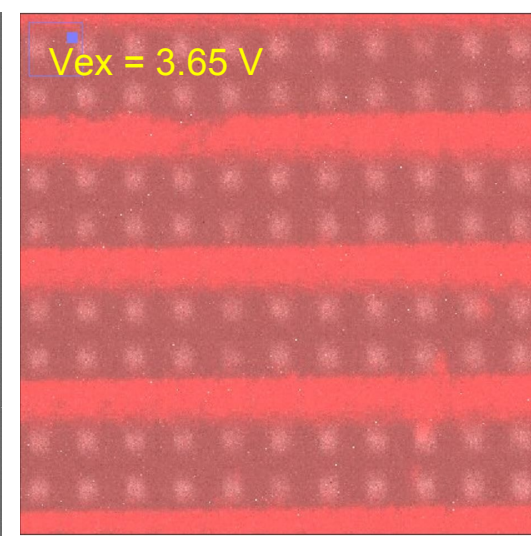
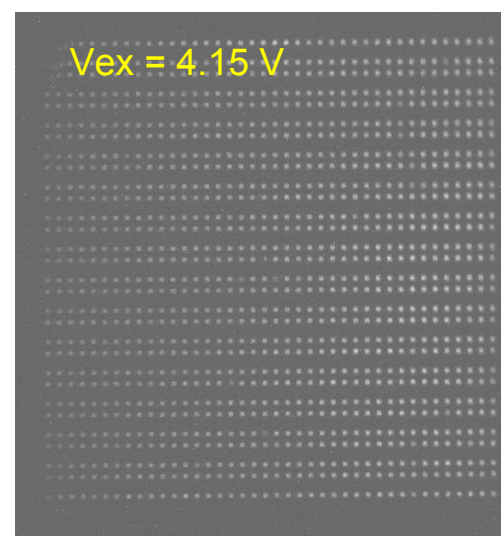
$V_{ex} = 1.8 \text{ V}$   
 $1\text{e}12 \text{ p/cm}^2$

$V_{ex} = 2.3 \text{ V}$   
 $1\text{e}12 \text{ p/cm}^2$

Damage produces hotspots across entire active area, similar to non-irradiated light emission.

# Gen5.1 non cap

Non-capacitor channels make it clear that the entire active area emits, and reveals that all exposed GaInP takes damage, alluding to lattice damage.



Do not know depth of damage.



# Conclusions

Functional Geiger-mode APDs can be made of GaInP

Images of light emission from the devices can be used to understand radiation damage and device active structure

GaInP APDs seem to show similar bulk damage effects to SiPMs, but are far less optimized devices / quality of materials

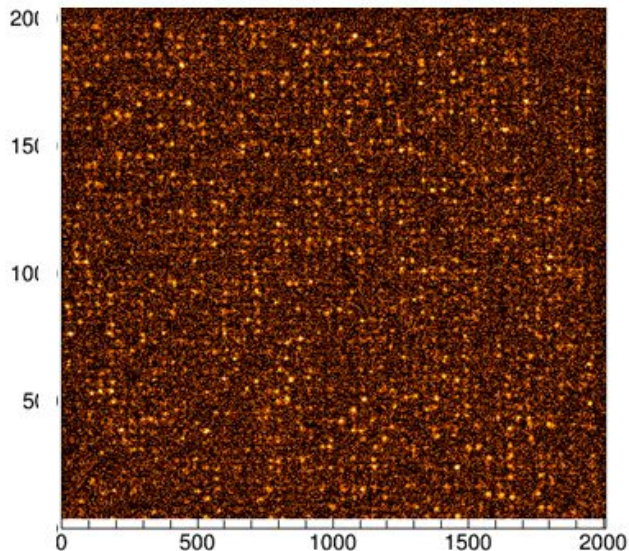
Gen 6 should arrive this summer, and we will continue radiation damage and light emission studies

More Information and Backup slides

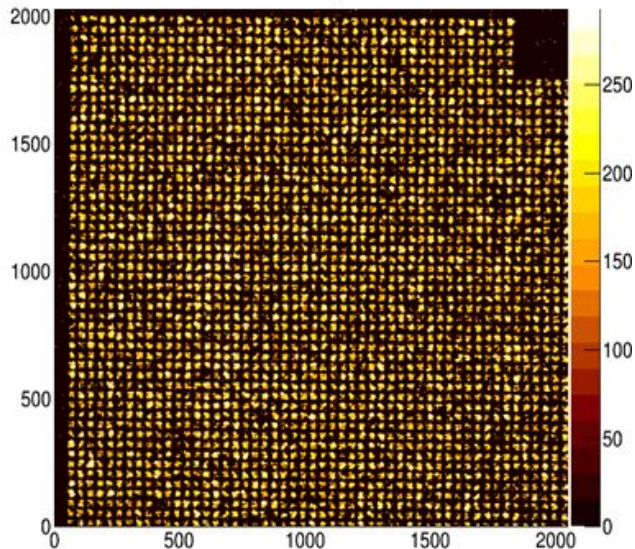
# SiPM Damage

**SiPM, Hamamatsu suggested  $V_{ex}$**

$3E10 \text{ p/cm}^2$



$1E12 \text{ p/cm}^2$



SiPMs also have hotspots uniformly distributed across the array.

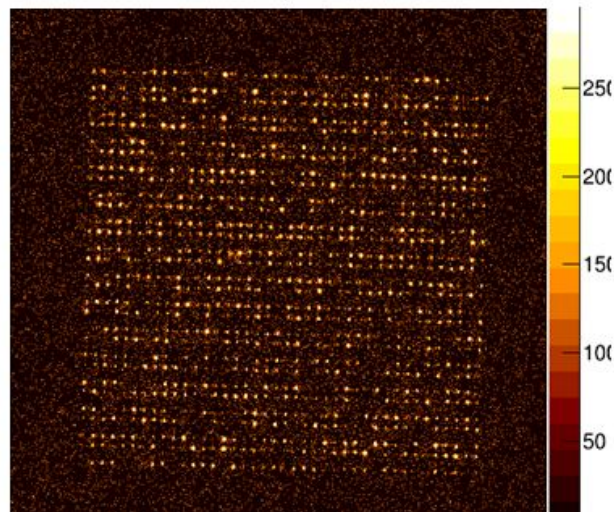
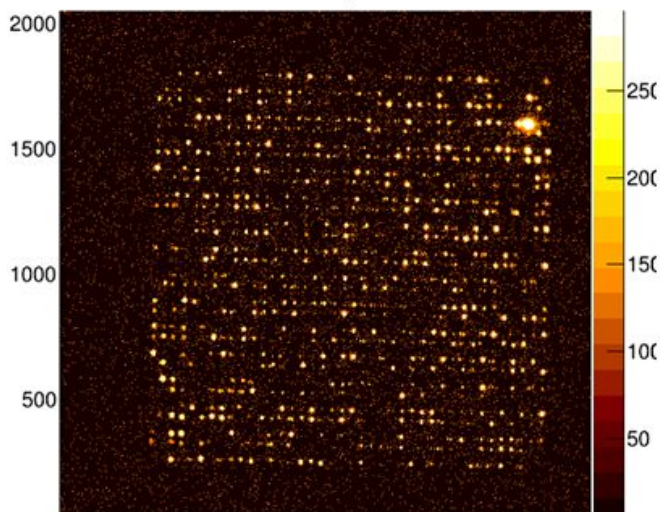
While the SiPM images have less light captured, SiPMs should emit farther into the infrared, which cannot be captured by our camera.

# Amount of light , Gen5.1

**Gen 5.1,  $V_{ex} = 0.5$  V**

1E11 p/cm<sup>2</sup>

1E12 p/cm<sup>2</sup>



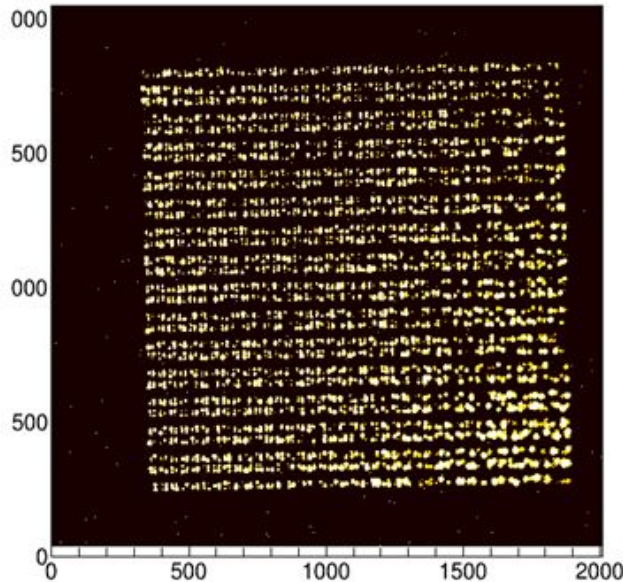
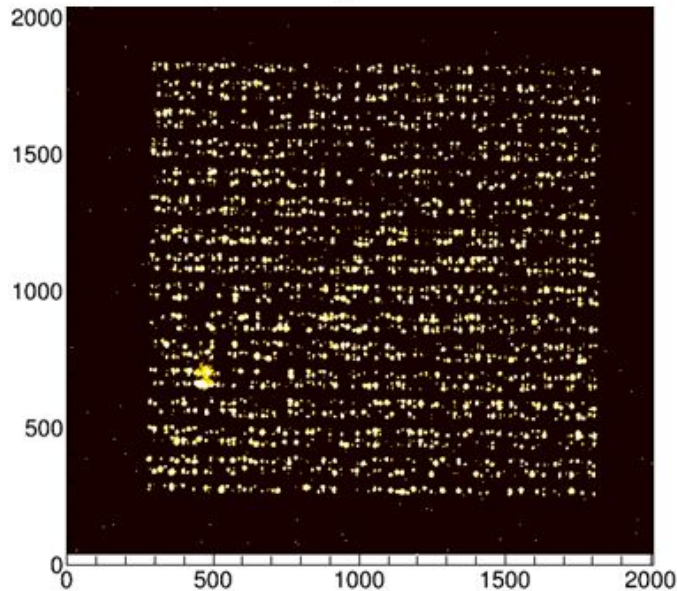
Hot spots burn brighter than SiPMs, but still comparable.

# Amount of Light, Gen5.2

**Gen 5.2,  $V_{\text{ex}} = 0.3 \text{ V}$**

$1\text{E}11 \text{ p/cm}^2$

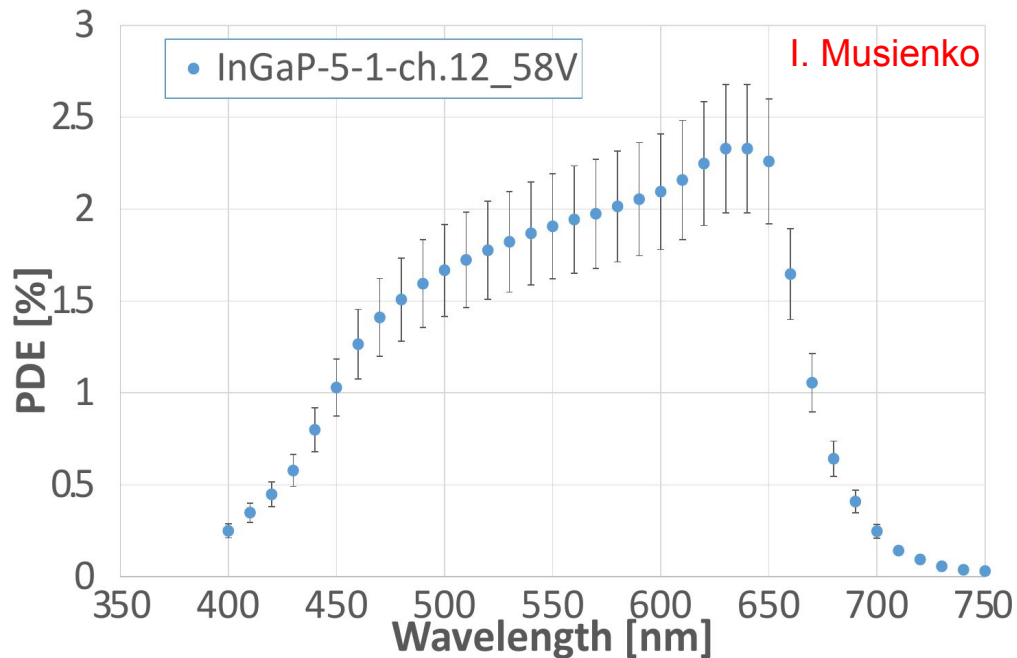
$1\text{E}12 \text{ p/cm}^2$



Much more light emission due to damage than Gen5.1 or SiPMs



# Photon Detection Efficiency



Gen5.1 non-capacitor channel

# Device Structure

